

ICS 31.200
CCS L 40



**NATIONAL STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

GB/T 42709.5-2023

**Semiconductor devices - Micro-electromechanical devices -
Part 5: RF MEMS switches**

Issued on: May 23, 2023

Implemented on: September 1, 2023

**Issued by: State Administration for Market Regulation, China National
Standardization Administration**

Table of Contents

Preface	
Introduction	
1 Scope	1
2 Normative references	1
3 Terms and Definitions	1
3:1 Switching terminology	2
3:2 Switch Structure Terminology	2
3:3 Terminology of drive mode	2
3:4 Switch Network Structure Terminology	2
3:5 Reliability Terminology	3
3:6 Terminology of electrical characteristics	3
4 Basic ratings and characteristics	5
4:1 Identification and type description	5
4:2 Applications and Specifications	5
4:3 Limit values and operating conditions	5
4:4 DC and RF characteristics	6
4:5 Mechanical and environmental characteristics	6
4:6 Additional information	6
5 Test method	6
5:1 General	6
5:2 DC characteristics	7
5:3 Radio frequency characteristics	10
5:4 Switching characteristics	14

foreword

This document is in accordance with the provisions of GB/T 1:1-2020 "Guidelines for Standardization Work Part 1: Structure and Drafting Rules for Standardization Documents"

drafting:

This document is part 5 of GB/T 42709 "Microelectronic Mechanical Devices for Semiconductor Devices": GB/T 42709 has been issued with

Lower part:

--- Part 5: RF MEMS switches;

--- Part 7: MEMS bulk acoustic wave filters and duplexers for radio frequency control and selection;

--- Part 19: Electronic compass:

This document is equivalent to IEC 62047-5:2011 "Microelectronic Mechanical Devices for Semiconductor Devices Part 5: RF MEMS

switch":

The following minimal editorial changes have been made to this document:

--- Incorporate the clauses involved in the contents of the IEC 62047-5:2011/Cor1:2012 errata:

Double lines (||) are marked:

--- Added Appendix NA (informative):

Please note that some contents of this document may refer to patents: The issuing agency of this document assumes no responsibility for identifying patents:

Introduction

This document is applicable to RF MEMS switches, and specifies the terms, definitions, Symbols and parameter testing methods, etc., are conducive to better guiding practitioners in related industries in product development, testing, and use:

GB/T 42709 "Microelectronic Mechanical Devices for Semiconductor Devices" is proposed to consist of the following parts:

--- Part 2: Tensile test methods for film materials: The purpose is to specify the tensile test method for MEMS thin film materials:

--- Part 3: Film standard test piece for tensile test: The purpose is to specify test pieces for tensile testing of MEMS thin film materials

related requirements:

--- Part 5: RF MEMS switches: The purpose is to specify the term definitions, characteristic requirements, and testing methods of RF MEMS switches:

law etc:

--- Part 6: Thin film material axial fatigue test method: The purpose is to specify the axial fatigue test of MEMS thin film materials

method:

--- Part 7: MEMS bulk acoustic wave filters and duplexers for radio frequency control and selection: The purpose is to specify the MEMS body

Definition of terms, characteristic requirements, test methods, etc: of acoustic wave resonators, filters and duplexers:

--- Part 8: Strip bending test method for the measurement of film tensile properties: The purpose is to specify the method used to measure the tensile properties of films

Strip bend test method:

--- Part 9: MEMS wafer bonding strength test method: The purpose is to specify the bonding strength test method for MEMS wafers:

--- Part 11: Test method for linear thermal expansion coefficient of suspended MEMS materials: The purpose is to specify the

Test method for coefficient of linear thermal expansion:

--- Part 12: Flexural fatigue test method for thin film materials using MEMS structural resonance method: The purpose is to specify MEMS thin

Membrane material flexural fatigue test method:

--- Part 13: MEMS structure adhesion strength test method: The purpose is to specify the adhesion strength test of MEMS structure

method:

--- Part 16: Wafer curvature and cantilever beam deflection test method for MEMS film residual stress: The purpose is to stipulate

Two test methods of wafer curvature and cantilever beam deflection for MEMS film residual stress:

--- Part 19: Electronic compass: The purpose is to specify the term definitions, characteristic requirements, test methods, etc: of the electronic compass:

--- Part 21: MEMS thin film material Poisson's ratio test method: The purpose is to specify the Poisson's ratio test of MEMS thin film materials

method:

--- Part 22: Electromechanical tensile test methods for conductive films on flexible substrates: The purpose is to specify the characteristics of MEMS conductive thin film materials

Tensile test method for electromechanical properties:

--- Part 26: Description and test methods of micro-grooves and needle structures: The purpose is to specify the description of MEMS microgroove and needle structure

description and test methods:

--- Part 27: MCT test method for bond strength of glass fused structures: The purpose is to specify the bond strength of the glass frit structure

Degree of MCT test method:

--- Part 29: Test method for electromechanical relaxation of suspended conductive films at room temperature: The purpose is to specify the suspended conductance of MEMS devices

Test method for electromechanical relaxation of electromechanical thin films at room temperature:

--- Part 32: MEMS resonator nonlinear vibration test method: The purpose is to specify the nonlinear vibration of MEMS resonators

performance testing method:

--- Part 35: Test methods for electrical characteristics of flexible electromechanical devices bending deformation: The purpose is to specify the bending deformation of flexible electromechanical devices

State electrical characteristics test method:

--- Part 36: Environmental and dielectric withstand test methods for MEMS piezoelectric films: The purpose is to specify the MEMS piezoelectric film

Environmental and dielectric withstand performance test methods:

--- Part 38: Test method for adhesion strength of metal powder paste in MEMS interconnection: The purpose is to specify the gold in the MEMS interconnection

It is a test method for the adhesion strength of powder paste:

--- Part 40: MEMS inertial shock switch threshold test method: The purpose is to specify the threshold of MEMS inertial shock switch

Test Methods:

Semiconductor Devices Micro-Electro-Mechanical Devices

Part 5: RF MEMS switches

1 Scope

This document defines the terms, definitions and symbols used to evaluate and determine the basic ratings and characteristics of RF MEMS switches, and describes

Parameter test method:

This document is applicable to various types of RF MEMS switches: See Appendix A for